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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/807,274	03/24/2004	Kazutaka Akiyama	04173.0446	3986
22852 75	590 08/28/2006		EXAMINER	
FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER			ANDUJAR, LEONARDO	
LLP 901 NEW YORK AVENUE, NW			ART UNIT	PAPER NUMBER
WASHINGTON, DC 20001-4413		2826		
			DATE MAILED: 08/28/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/807,274	AKIYAMA, KAZUTAKA				
Office Action Summary	Examiner	Art Unit				
	Leonardo Andújar	2826				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period was realized to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be timused and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 11 At	-					
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	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
closed in accordance with the practice under E	:x pane Quayle, 1935 C.D. 11, 45	03 O.G. 213.				
Disposition of Claims						
4) Claim(s) 1-20 is/are pending in the application.						
4a) Of the above claim(s) <u>3-6,8,10,12,14 and 16-20</u> is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6) Claim(s) 1,2,7,9,11,13 and 15 is/are rejected.						
7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or	r election requirement					
or claim(s) are subject to restriction and/or	r election requirement.					
Application Papers						
9) The specification is objected to by the Examine	r.					
10) The drawing(s) filed on is/are: a) acce						
Applicant may not request that any objection to the						
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex						
Priority under 35 U.S.C. § 119						
12)⊠ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a)⊠ All b)□ Some * c)□ None of:						
1. Certified copies of the priority documents have been received.						
 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage 						
_ ,	•	ed in this National Stage				
application from the International Bureau * See the attached detailed Office action for a list		ad.				
occ the attached detailed Office action for a fist	or the defined doples not receive	.a.				
Attachment(s)						
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) 	4) 🔲 Interview Summary Paper No(s)/Mail D					
Notice of Dransperson's Patent Drawing Review (P10-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 3/04;6/05;02/06.		Patent Application (PTO-152)				

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DETAILED ACTION

Election/Restrictions

1. Applicant's election without traverse of claims 1, 2, 7, 9, 11, 13 and 15 in the reply filed on 08/11/2006 is acknowledged.

Priority

2. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

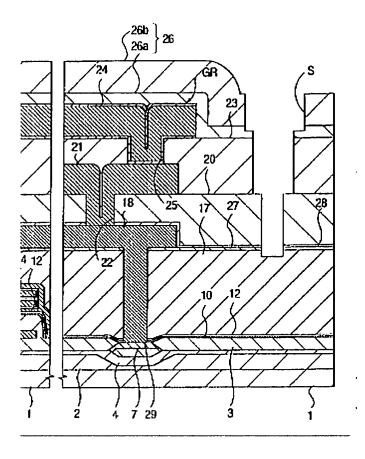
Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims1, 2, 7, 9, 11, 13 and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Suwanai et al. (US 5,994,762) in view of Wolf further in view of Kishida (US 6,770,977).
- 5. Regarding claims 1, 2, 13 and 15, Suwanai (e.g. fig. 11) shows a semiconductor device comprising: a semiconductor substrate 1; a first insulating film 17/27 formed above the semiconductor substrate and having a relative dielectric constant; a conductor 18 (e.g. aluminum/tungsten, col. 2/lls. 5-11) which covers a side face of the first insulating film at least near four corners of the semiconductor substrate (note that 18 is part of a guard ring GR, see fig. 3),

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and a second insulating film 20 covering the outer side face of the conductor and having a relative dielectric constant of over 3.8 (inherent property of BPSG).



Suwanai does not teach that the first insulating layer has a relative dielectric constant of less than 3.8 nor a barrier layer on the at least an outer side face. Nevertheless, Wolf teaches that integrated circuits include a plurality of devices interconnected by multilevel interconnections including dielectric layers (pg 716-727). Also, the interconnect delay can be reduced by using low k dielectric material (e.g. nanoporous silica (SiO₂) "ultra low") having a dielectric

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constant of less than 2.0 (pgs. 791-795). Kishida (e.g. fig. 8b) teaches a barrier

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layer 202/203 composed tantalum nitride/tantalum is formed on an outer surface

a conductor layer to prevent the metal atoms of the conductive layer from

diffusing to the semiconductor substrate (col. 2/lls. 50-59 7 col. 8/lls. 26-28). It

would have been obvious to one of ordinary skill in the art at the time the

invention was made to use a low k dielectric material (e.g. nanoporous silica

SiO₂) having a dielectric constant of less than 2.0 for the first dielectric layer

disclosed by Suwanai in order to reduce the interconnect delay as taught by Wolf

and to include a barrier layer on an outer surface a conductor layer disclosed by

Suwanai in view of Wolf to prevent the metal atoms of the conductive layer from

diffusing into the semiconductor substrate.

6. Regarding claim 7, Suwanai shows that the second insulating film also

covers an upper side of the first insulating film and a conductor 21 passing

through the second insulating film positioned on the upper side of the first

insulating film.

7. Regarding claim 9, Suwanai shows a conductive pattern buried in the first

insulating film (e.g. 11, 15).

8. Regarding claim 11, Suwanai shows that the first insulating film is

constituted of a plurality of layers 17/27.

Conclusion

9. Any inquiry concerning this communication or earlier communications from

the examiner should be directed to Leonardo Andújar whose telephone number

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is 571-272-1912. The examiner can normally be reached on Mon through Thu

from 9:00 AM to 7:30 PM EST.

If attempts to reach the examiner by telephone are unsuccessful, the

examiner's supervisor, Nathan J. Flynn can be reached on 571-272-1915. The

fax phone number for the organization where this application or proceeding is

assigned is 571-273-8300.

Information regarding the status of an application may be obtained from

the Patent Application Information Retrieval (PAIR) system. Status information

for published applications may be obtained from either Private PAIR or Public

PAIR. Status information for unpublished applications is available through

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Representative or access to the automated information system, call 800-786-

9199 (IN USA OR CANADA) or 571-272-1000.

eonardo Andúja

Primary Examiner

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08/18/2006